

June 30 (Tue)	Time	July 1 (Wed)	July 2 (Thu)	July 3 (Fri)
	8:20-8:40	Registration (Foyer)	Registration (Foyer)	Registration (Foyer)
	8:40-9:20		[HP1] Chair: Takeo Nakano (Seikei University)	[AP1] Chair: Ralf Bandorf (Fraunhofer Institute for Surface Engineering and Thin Films)
			[HP1-01] <Keynote> <i>High Power Impulse Magnetron Sputtering: From fundamental concepts to industrial applications</i> Ralf Bandorf (Fraunhofer Institute for Surface Engineering and Thin Films)	[AP1-01] <Keynote> <i>Interconnect technologies for beyond 2nm integration</i> Kazuyoshi Ueno (Yokohama National University)
	9:20-9:40	Opening @ Science Hall	[HP1-02] Stanislava Debnarova (Masaryk University)	[AP1-02] Hee Yeon Noh (Daegu Gyeongbuk Institute of Science & Technology, DGIST)
	9:40-10:00	[TF1] Chair: Junichi Nomoto (National Institute of Advanced Industrial Science and Technology)	[HP1-03] Younes Lablali (Mohammed VI Polytechnic University)	[AP1-03] Azusa N. Hattori (I-PEX Piezo Solutions Inc.)
		[TF1-01] <Keynote> <i>Analysis of heating processes during film growth by sputter deposition</i> Andre Anders (Plasma Engineering LLC)		
	10:00-10:20		[HP1-04] <Industrial> Johan Böhlmark (Ionautics AB)	[AP1-04] <Industrial> Masaaki Matsukuma (Tokyo Electron Technology Solution Ltd.)
	10:20-10:40	Coffee Break (Foyer)	Coffee Break (Foyer)	Coffee Break (Foyer)
	10:40-11:10	[TF2] Chair: Jinn P Chu (National Taiwan University of Science & Technology)	[HP2] Chair: Tetsuhide Shimizu (Tokyo Metropolitan University)	[SP2] Chair: Naho Itagaki (Kyushu University)
		[TF2-01] <Invited> <i>Real-time monitoring of stress evolution during sputter-deposition of elemental and alloy thin films</i> Gregory Abadias (Institut Pprime/ University of Poitiers)	[HP2-01] <Invited> <i>The high power impulse magnetron sputtering discharge</i> Jon Tomas Gudmundsson (University of Iceland)	[SP2-01] <Invited> <i>Double Ring Magnetron sputtering – Superior process control for high-rate, stress-controlled, single-phase AlScN piezoelectric layers and polarity controlled AlN epitaxy</i> Elizabeth von Hauff (Fraunhofer Institute for Electron and Plasma Technology)
	11:10-11:30	[TF2-02] Farzaneh Farahani (Ghent University)	[HP2-02] Charles Ballage (LPGP/ Université Paris Saclay)	[SP2-02] Jia-Qi Xu (Jimei University)
	11:30-11:50	[TF2-03] Naofumi Ohtsu (Kitami Institute of Technology)	[HP2-03] Erdong Chen (Tokyo Metropolitan University)	[SP2-03] Deniz Gamze Sanal (Faraday Factory Japan)
	11:50-12:10	[TF2-04] Jocelyn Kezia Sutadharma (Kyushu University)	[HP2-04] Ismail Rahmadtulloh (Chang Gung University)	[SP2-04] <Industrial> Dermot Patrick Monaghan (Genco Ltd.)
Tutorial Reception (Foyer)	12:10-12:30	[TF2-05] <Industrial> Takehito Jinbo (ULVAC, Inc.)	[HP2-05] <Industrial> Kenji Fuchigami (IHI Hauzer Techno Coating Japan)	[SP2-05] <Industrial> Kun Zhang (Optorun Co., Ltd.)
	12:30-13:00	Lunch Break	Lunch Break	Lunch Break
ISSP Special Tutorial	13:00-13:40			

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ISSP Special Tutorial (Room G) (~17:00) "Coating materials design" by Prof. Jochen M. Schneider (RWTH Aachen University)	13:40-14:10	[FA1] Chair: Jochen M Schneider (RWTH Aachen University)	[SP1] Chair: Andre Anders (Plasma Engineering LLC)	Poster Session & Exhibition (Atrium)
		[FA1-01] <Invited> <i>Defect- and interface-engineered ceramic thin films for extreme environments</i> Paul H. Mayrhofer (TU Wien)	[SP1-01] <Invited> <i>Manipulating spokes in magnetron sputtering discharges</i> Martin Rudolph (Leibniz Institute of Surface Engineering)	
	14:10-14:40	[FA1-02] <Invited> <i>Evolution in microstructure and mechanical properties of magnetron sputtering refractory metal nitride hard coatings through plasma control</i> Fan-Bean Wu (National United University)	[SP1-02] <Invited> <i>Knowledge-based radio-frequency plasma processing</i> Hyo Chang Lee (Korea Aerospace University)	
	14:40-14:50	[FA1-03] Matej Fekete (Masaryk University)	[SP1-03] Andrey Kaziev (National Research Nuclear University, MEPhI)	Coffee Break (Foyer) (~14:50)
	14:50-15:00			[AP2] Chair: Stephanos Konstantinidis (University of Mons)
	15:00-15:20	[FA1-04] Tomáš Fiantok (Comenius University Bratislava)	[SP1-04] Peter Klein (Masaryk University)	[AP2-01] <Invited> <i>Triboelectrification at solid-liquid interfaces: Surface chemistry-driven charge transfer for self-powered nanosensing</i> Zong-Hong Lin (National Taiwan University)
	15:20-15:40	Coffee Break (Foyer)	Coffee Break (Foyer)	[AP2-02] <Invited> <i>Controlled growth of sculptured thin films via sputtering-GLAD for advanced sensing applications</i> Mati Horprathum (National Electronics and Computer Technology Center, NECTEC)
	15:40-15:50	[TF3] Chair: Kunio Okimura (Tokai University)	[FA2] Chair: Takayuki Kiba (Kitami Institute of Technology)	
	15:50-16:10	[TF3-01] <Invited> <i>Heteroepitaxial growth of polar, semipolar, and nonpolar ScGaN thin films on sapphire substrates by magnetron sputter epitaxy</i> Ching Lien Hsiao (Linköping University)	[FA2-01] <Invited> <i>Sputtering Atomic Layer Augmented Deposition (SALAD): A Versatile approach to tailor dielectric/metal systems for cross-disciplinary optical applications</i> Nobuhiko Paul Kobayashi (University of California Santa Cruz)	[AP2-03] Andrey Ushakov (TNO Netherlands Organization for Applied Scientific Research)
		[TF3-02] Marek Bouska (University of Pardubice)	[FA2-02] Stephanos Konstantinidis (University of Mons)	[AP2-04] Helmi Son Haji (National Taiwan University of Science &Technology)
	16:30-16:50	[TF3-03] Jochen M Schneider (RWTH Aachen University)	[FA2-03] Yasuhiro Tomioka (Kanazawa University)	[AP2-05] Eiji Kusano (Kanazawa Institute of Technology)
	16:50-17:10	[TF3-04] <Industrial> Ken Mita (Kobe Steel, Ltd.)	[FA2-04] Andrey Shukurov (Charles University)	Awards & Closing Ceremony (Science Hall)
	17:10-17:30	[TF3-5] <Industrial> Hisashi Kitami (Sumitomo Heavy Industries, Ltd.)	[FA2-05] <Industrial> Waldemar Schönberger (Von Ardenne GmbH)	
	17:40-19:10	Poster Session & Exhibition (Atrium)	Poster Session & Exhibition (Atrium)	